

Application No.: 10/706,423

Attorney Docket No.: FUK-140

Response Dated: December 13, 2004

Reply for Notice to File Corrected Application Papers dated: September 14, 2004

LISTING OF THE CURRENT VERSION OF THE CLAIMS

Claims 1-33 (canceled)

Claim 34 (original): A plasma processing method using a plasma device comprising a container, the inside of which can be internally decompressed, and part of the inside being formed of a first dielectric plate made of material capable of passing microwaves with almost no loss, a gas supply system for supplying essential source material gas so as to cause excitation of plasma inside the container, an exhaust system for expelling source material gas that has been supplied inside the container and decompressing the inside of the container, an antenna, located facing an outer surface of the first dielectric plate and comprised of a slot plate and a waveguide dielectric, for radiating microwaves, and an electrode for holding an object to be treated located inside the container, a surface of the object to be treated that is to be subject to plasma processing and a microwave radiating surface of the antenna being arranged in parallel substantially opposite to each other, and the plasma device carrying out plasma processing for the object to be treated, the power density of microwaves to be input being 1.2 W/cm² or more.

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Claim 35 (previously presented): The plasma processing method as disclosed in claim 34, wherein a pressure of the space between the first dielectric plate and the second dielectric plate is made higher than a pressure of a space, in which the electrode for holding the object to be treated is located, and which is surrounded by the second dielectric plate and a wall section of the container other than the second dielectric plate.

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Claims 36-73 (canceled)